

the manufacture of the object, the selected components being other than ellipsometric angles ψ and Δ and the trigonometric functions of the ellipsometric angles ψ and Δ ;

making an ellipsometric measurement of object during manufacture;

extracting, from the ellipsometric measurement, only the determined selected components of the Mueller matrix; and

controlling the manufacture of the object in relation to the extracted components of the Mueller matrix.--

Amend C2
[Amend claim 22 as follows:]

--22. (amended) An installation for making anisotropic objects and making depolarizing objects, comprising:

an ellipsometer configured to make an ellipsometric measurement of an object during manufacture;

a processor configured to extract, from the ellipsometric measurement, only determined selected components of the Mueller matrix that represents the object and that characterizes the manufacture of the object,

the processor also configured to control the manufacture of the object in relation to the extracted components of the Mueller matrix, wherein,

the determined selected components are at least two selected components of the Mueller matrix that characterize the manufacture of the object, and

Amended
C2

the determined selected components are other than ellipsometric angles ψ and Δ and trigonometric functions of the ellipsometric angles ψ and Δ .--

Amend claim 24 as follows:

--24. (amended) A manufacturing installation, comprising:

C3

a plasma chamber (1) with power control;

a support (3) within the chamber for supporting a substrate (2) serving as an original element of a solid-state wafer to be manufactured;

a pump (4) connected to the chamber to maintain a pressure within the chamber;

a gas panel (6) connected to the chamber to supply the chamber with gas, the gas panel having plural gas inputs (62-65), each gas input connected to the chamber via a flow-meter (621, 631, 641, 651) and a valve (622, 632, 642, 652);

an ellipsometer (9) comprising a transmission head (91) and a receiving assembly (92), the ellipsometer arranged to control the gas panel to control a preparation of layers on the substrate based on ellipsometric measurement of the substrate,

the transmission head comprising a phase modulator,

the receiving assembly comprising a polarizer-analyzer;

a first processing unit (93) connected to the transmission head to control the phase modulator, and connected